a base substrate having a plurality of deposits each comprising a pharmaceutically active ingredient, the deposits being disposed on discrete regions of a first surface of the base substrate and being formed by generating an electrostatic force at said discrete regions, and directing a cloud of charged grains towards said first surface of the base substrate; and

a cover substrate that overlies the plurality of depositions and is joined to the first surface of the base substrate by bonds that individually surround each of said depositions, the active ingredient in each deposition being present in an amount that does not vary from a target amount by more than about 5 weight percent.

37. The product of claim 36, wherein the cover substrate has a planar form that includes a plurality of concavities, each concavity overlying a deposit, and further wherein the bonds individually surround each concavity.

REMARKS

Claims 1-10, 17-19 and 21-37 are active. Claims 11-16 and 20 are canceled.

Claims 21-37 are new. This amendment is preliminary and accompanies a continuation application.

Amendment is made to certain of the claims and to the specification to add the relevant serial and patent numbers of the various applications noted in the specification and to correct a typographical error. Enclosed is a copy of the amended claims marked up in red ink to show the changes. The claims are believed allowable.

Mlodozeniec is foreign to the claims as this reference does not disclose or suggest the claim 1 structure:

said at least one active ingredient being present in each of the unit forms in an amount which does not vary from a predetermined target amount by more than about 5 weight per cent.

This reference does not disclose enabling apparatus to produce such structure.

The remaining claims all include similar structure or corresponding step and are believed allowable for similar reasons.

Entry of this amendment is respectfully requested.

Respectfully submitted,

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